

In the Abstract:

Please amend the Abstract as follows:

A resistor and a structure ~~method and structure~~ for changing an electrical resistance of a resistor. Initially, the resistor is provided, wherein the resistor has a length L and an electrical resistance R_1 . A portion of the resistor is exposed to a laser radiation, wherein the portion includes a fraction F of the length L of the resistor. ~~Both $F = 1$ and $F < 1$ are within the scope of the present invention.~~ After the resistor has been exposed to the laser radiation, the resistor has an electrical resistance R_2 , wherein R_2 is unequal to R_1 . ~~The change in resistance from R_1 to R_2 is due to a heating of the resistor by the laser radiation, which causes a chemical or structural change within the resistor. Either $R_2 > R_1$ or $R_2 < R_1$ depending on the material composition of the resistor.~~